

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	392	(semiconductor adj substrate) same (first adj mask) same (second adj mask)	USPAT	OR	ON	2005/07/19 13:06
L2	884	(semiconductor adj substrate) same (first adj mask) same (second adj mask)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 13:06
L3	381	2 and implant\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 13:19
L4	0	3 and (floating adj mask)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 13:19
L5	44	(floating adj mask)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 14:26
L6	35	(suspended adj mask)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 13:25
L7	33	6 not 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 13:25
L8	2198	438/510.ccls. or 438/514.ccls. or 438/531.ccls. or 438/533.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 13:36
L9	712	438/510.ccls. or 438/514.ccls. or 438/531.ccls. or 438/533.ccls.	USPAT	OR	ON	2005/07/19 13:47

L10	20847	(floating or shadow or suspended) near mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 14:27
L11	20439	(floating or shadow or suspended) adj mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 14:27
L12	2135	11 and ((first and second) with mask)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 14:28
L13	138	12 and implant\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/19 17:16
L14	8	((("6085413") or ("5464521") or ("6920417") or ("6878577") or ("6645820") or ("6635558") or ("6624030") or ("6313905")).PN.	USPAT	OR	OFF	2005/07/19 17:41
L15	584	(first adj mask) and (second adj mask) and implant\$3	US-PGPUB	OR	ON	2005/07/19 17:52
L16	4	15 and ((floating adj mask) or (suspended adj mask) or (shadow adj mask))	US-PGPUB	OR	ON	2005/07/19 17:53
L17	3	15 and (implant\$3 near insulat\$3)	US-PGPUB	OR	ON	2005/07/19 17:44
L18	250	15 and (implant\$3 same insulat\$3)	US-PGPUB	OR	ON	2005/07/19 17:44
L19	1420	(first adj mask) with (second adj mask)	US-PGPUB	OR	ON	2005/07/19 17:52
L20	54	(first adj mask) with (second adj mask) with implant\$3	US-PGPUB	OR	ON	2005/07/19 17:52
L21	153	(first adj mask) same (second adj mask) same implant\$3	US-PGPUB	OR	ON	2005/07/19 17:53
L22	0	21 and ((floating adj mask) or (suspended adj mask) or (shadow adj mask))	US-PGPUB	OR	ON	2005/07/19 17:53
L23	101	21 and semiconductor adj substrate	US-PGPUB	OR	ON	2005/07/19 17:53